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Outstanding Reviewers for *Industrial Chemistry & Materials* in 2023

This article celebrates the Outstanding Reviewers for *Industrial Chemistry & Materials* in 2023.

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We would like to take this opportunity to thank all reviewers of *Industrial Chemistry & Materials* (ICM) reviewers for their dedication to enhancing the quality of papers and advancing scientific progress. We would also like to highlight the Outstanding Reviewers for ICM journal in 2023. Each of our outstanding peer reviewers has been carefully selected by our editorial team, based on the number, timeliness, and quality of their reports completed during 2023.

Annually, we announce our Outstanding Reviewers, recognizing those who have made significant contributions to peer review and gone above and beyond in their actions. Each of these experts receives a certificate to honor their valuable contributions. Drawing upon their professional expertise, these experts provide authors and editors with invaluable critical insights and constructive feedback.

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We would also like to thank the *Industrial Chemistry & Materials* Editorial Board and Advisory Board and the industrial chemistry and materials community for their continued support of the journal, as authors, reviewers and readers.

We continue to work on improving the diversity of our reviewer pool to reflect the diversity of the communities that we serve.

Suojiang Zhang, Editor-in-Chief
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